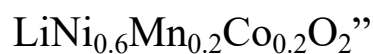


Supplementary Information for “Correlated biphasic features of  
the improved rate capability upon Ga doping in



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Table S1. 100 cycle capacity retention of NCM622 with and without Ga doping in the voltage range of 2.7-4.5 V

Ga content	0%	0.5%	1%	3%
Retention	68.47%	66.91%	80.46%	80.82%

Table S2. 100 cycle capacity retention of NCM622 with and without Ga doping in the voltage range of 3.5-4.3 V

Ga content	0%	0.5%	1%	3%
Retention	72.97%	90.09%	92.36%	91.41%

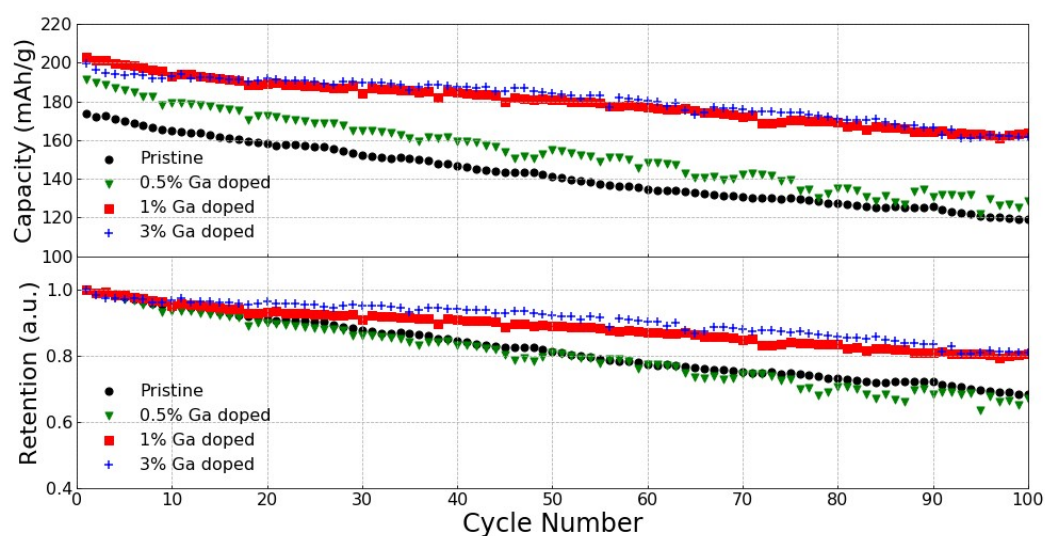


Figure S1. (a) Cyclic discharge capacity, (b) capacity retention, at 1 C of Ga doped and undoped NCM622 in the voltage range of 2.7-4.5 V.

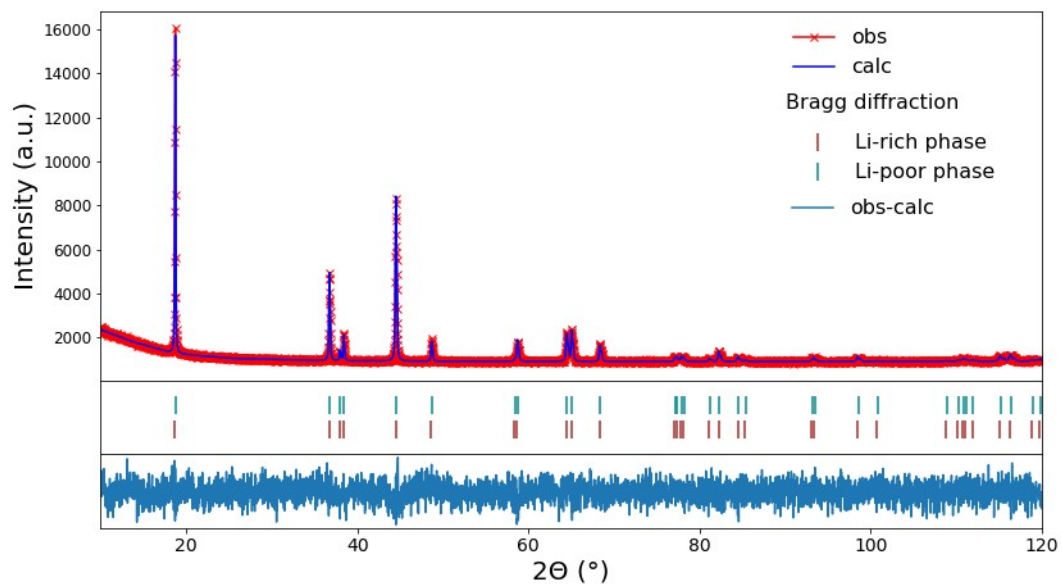


Figure S2. Rietveld refinement of XRD pattern for NCM622 without Ga doping.

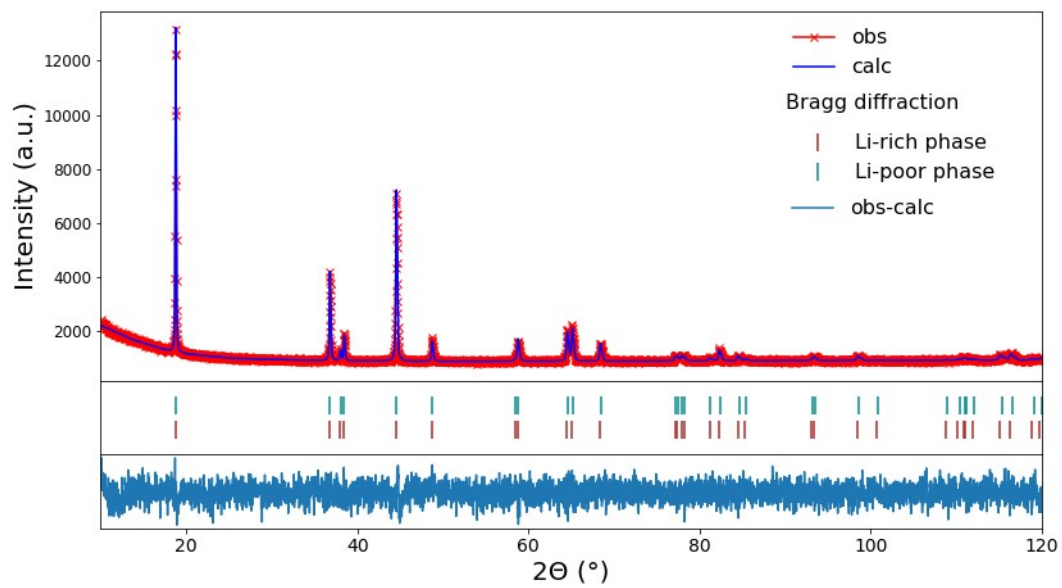


Figure S3. Rietveld refinement of XRD pattern for NCM622 with 0.5% Ga doping.

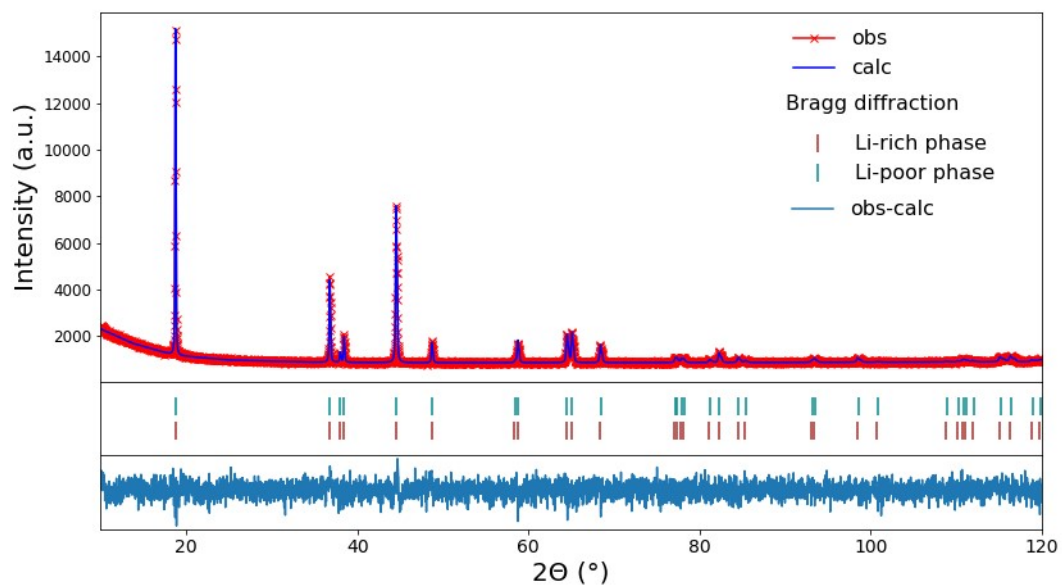


Figure S4. Rietveld refinement of XRD pattern for NCM622 with 1% Ga doping.

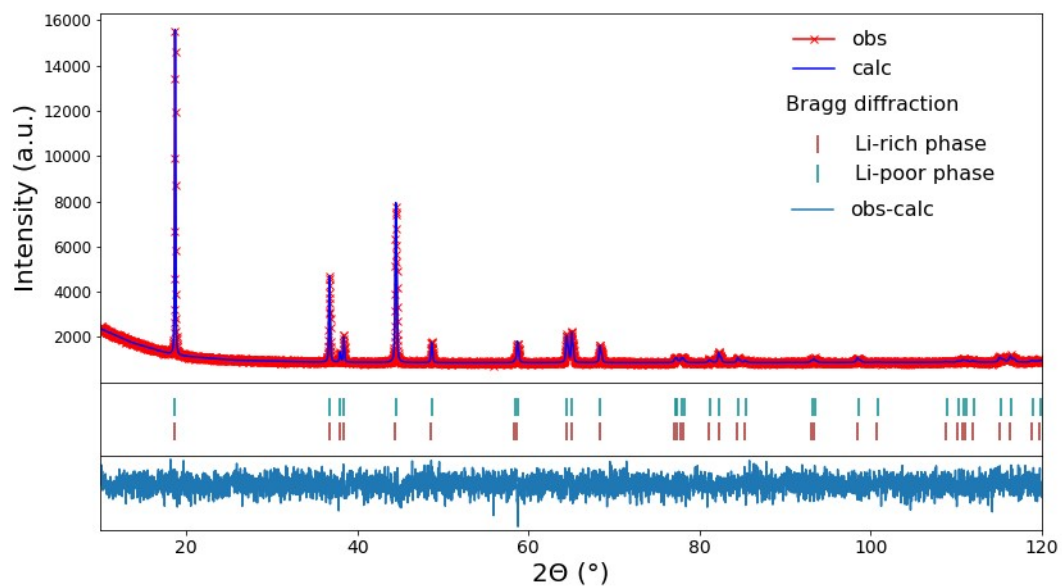


Figure S5. Rietveld refinement of XRD pattern for NCM622 without Ga doping.

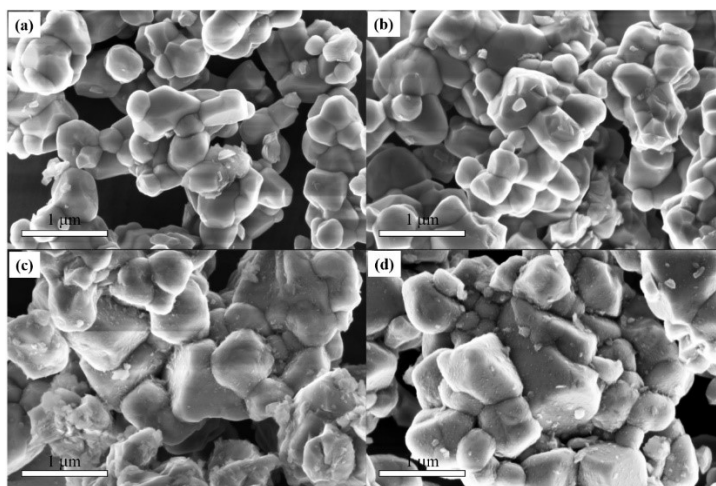


Figure S6. SEM micrographs of (a) 0%, (b) 0.5%, (c) 1%, (d) 3% Ga doped NCM622.

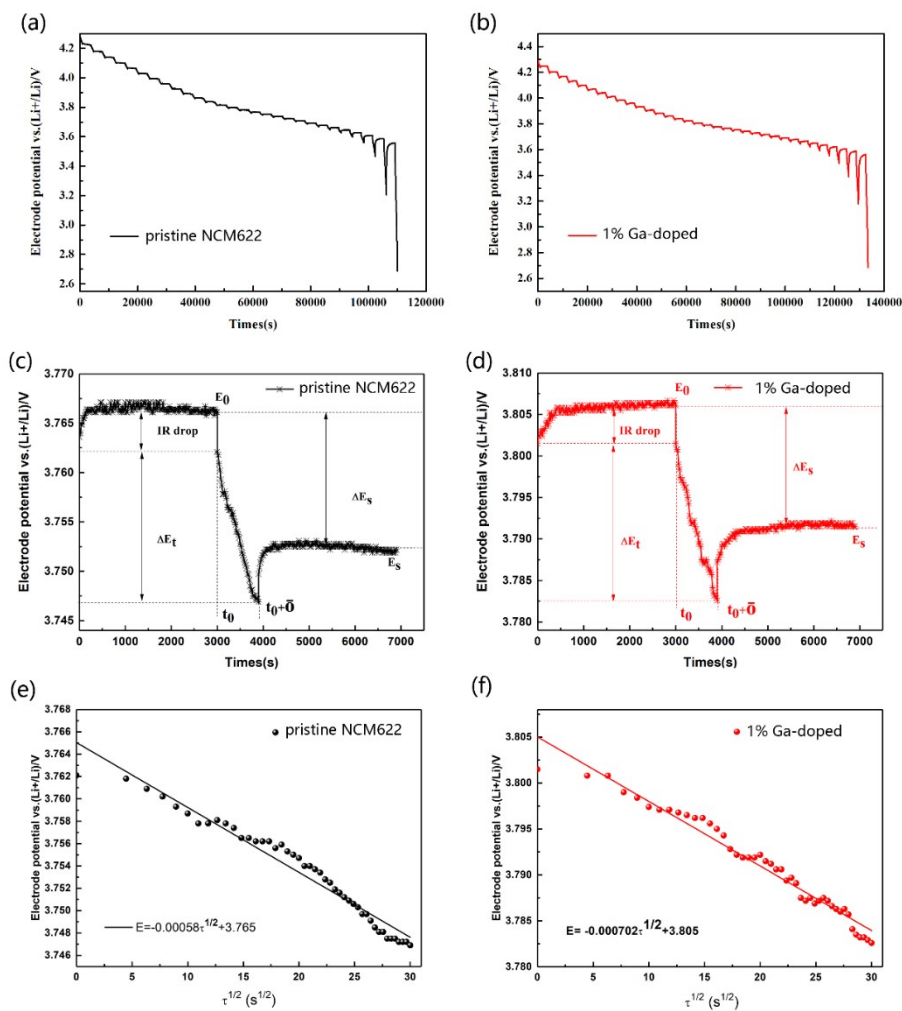


Figure S7. (a-b) GITT curves for the discharge of the prepared samples, (c-d) applied current plus vs cell voltage for a single titration step of GITT curves, (e-f) linear fit of the cell voltage as a function of the square root of time ( $\tau^{1/2}$ ) with different pulse current.

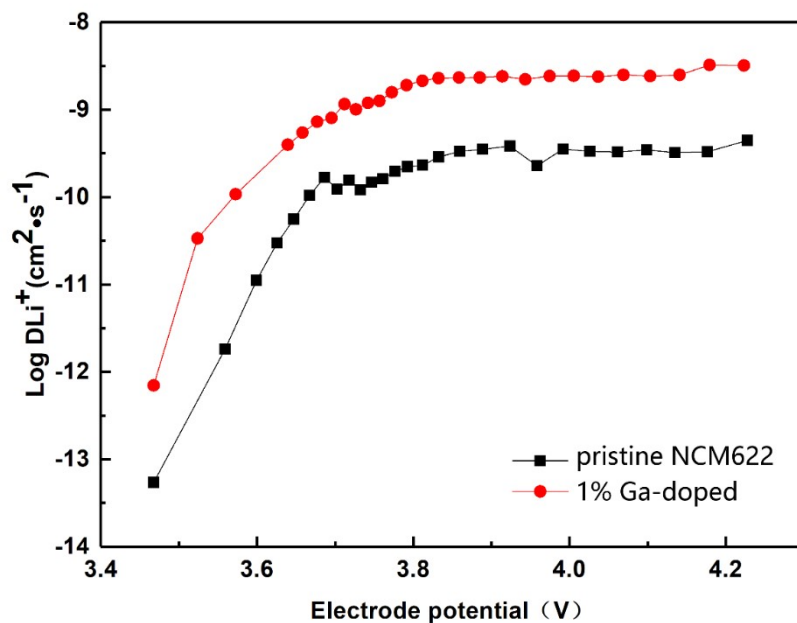


Figure S8. The chemical diffusion coefficient of  $\text{Li}^+$  as function of potential for NCM622 with and without Ga doping during discharge process.

Table S3. Calculated diffusion coefficient from EIS for NCM622 with and without Ga doping.

Ga content	Diffusion coefficient ( $\text{cm}^2/\text{s}$ )	
	Before cycling	After 100 cycles
0%	$1.28 \times 10^{-9}$	$6.31 \times 10^{-10}$
1%	$1.567 \times 10^{-9}$	$9.48 \times 10^{-10}$